

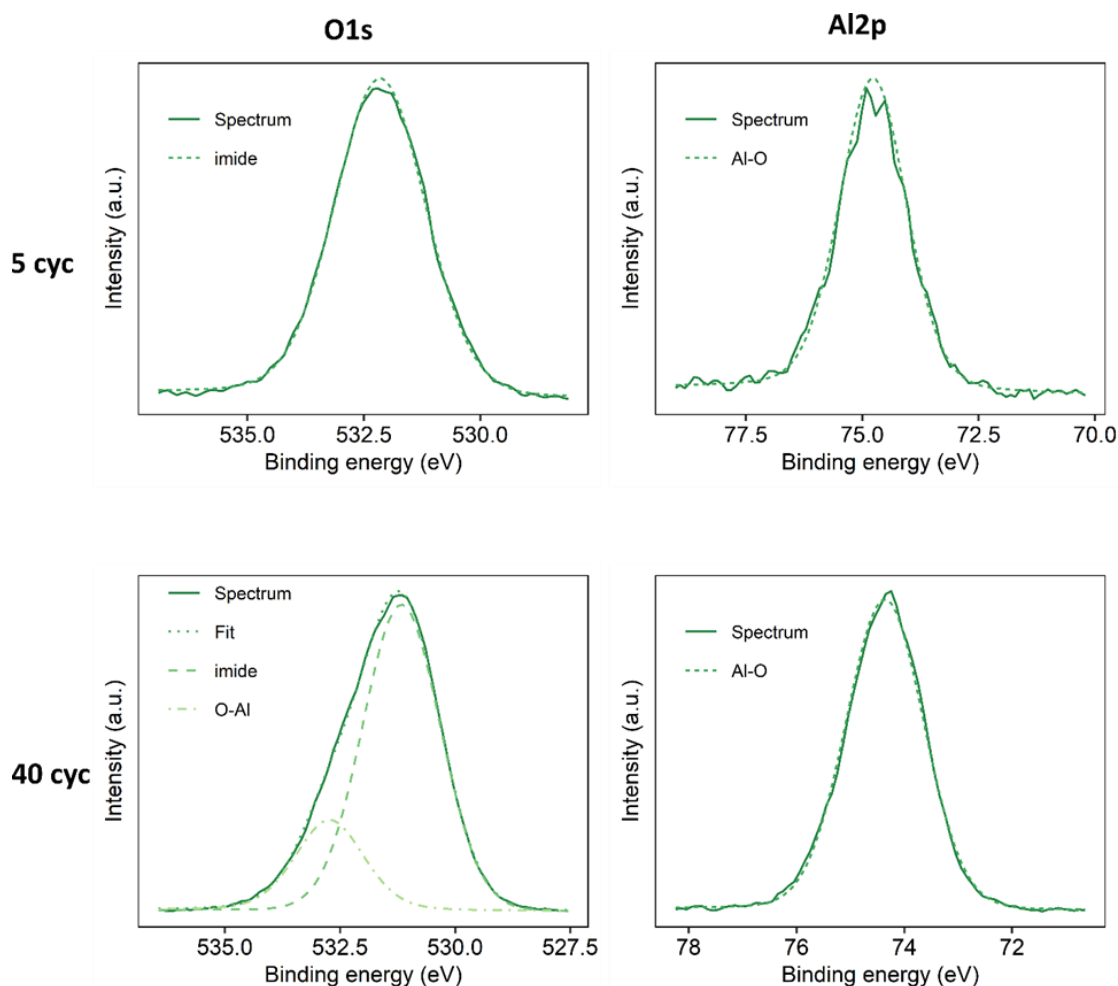
# Supplementary Materials: Investigating the Nucleation of AlO<sub>x</sub> and HfO<sub>x</sub> ALD on Polyimide: Influence of Plasma Activation

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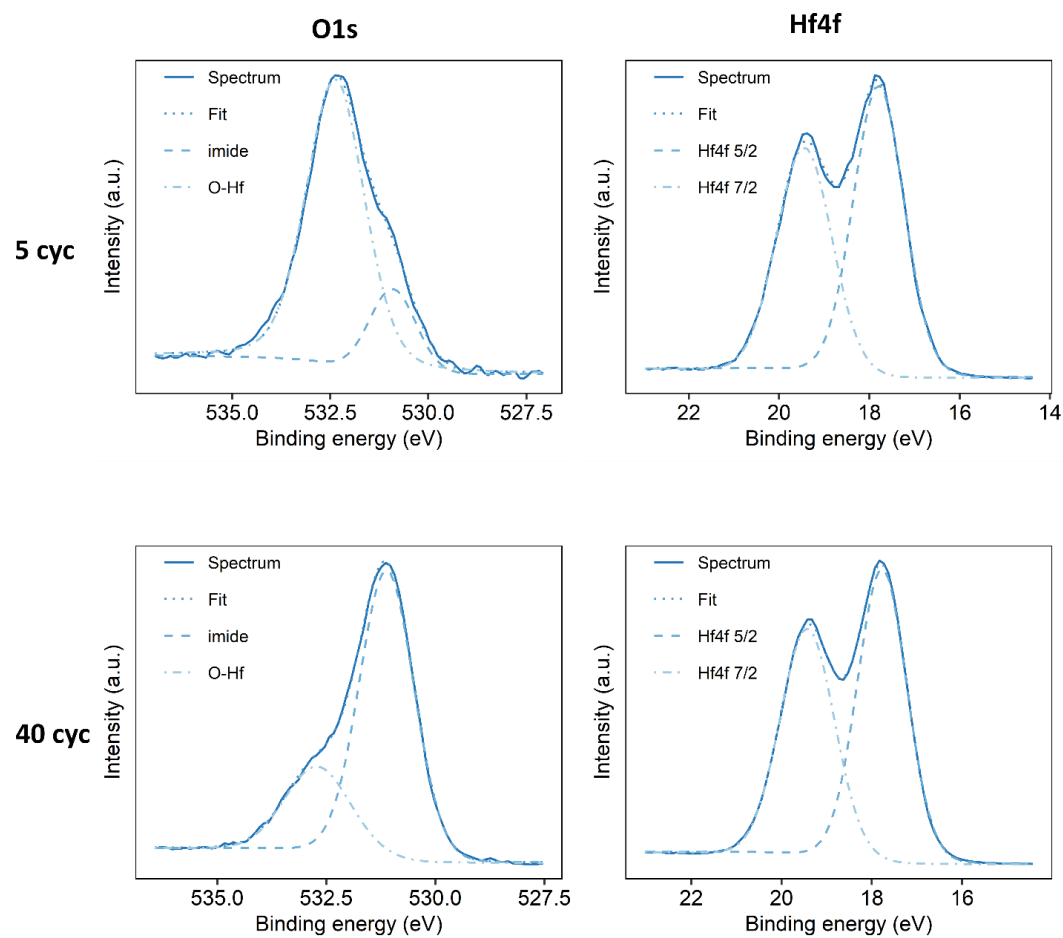
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**Figure S1.** Peak fitting of O1s and Al2p high resolution spectra after 5 and 40 ALD cycles of Al<sub>2</sub>O<sub>3</sub> on polyimide.



**Figure S2.** Peak fitting of O1s and Hf4f high resolution spectra after 5 and 40 ALD cycles of HfO<sub>2</sub> on polyimide.